



## Seiji Samukawa

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Joined NEC in 1981 after graduating in Instrumentation Engineering from Keio University. Worked on the research and development of ultra-precise plasma etching processes for ULSI devices. Promoted to Principal Researcher in Microelectronics Laboratory, R&D Group NEC Corporation. Obtained a Ph.D. in Instrumentation Engineering from Keio University in 1992. From July 2000 to July 2022, he had been a full professor at Tohoku University, an institution renowned for contributions to damage-free process and leading edge device technology, where he was Director of the Innovative Energy Research Center at the Institute of Fluid Science (IFS) Tohoku University and also Chair Professor of Taiwan National Yang Ming Chiao Tung University. Since August 2022, he has been a full professor at Taiwan National Yang Ming Chiao Tung University, famous as a cutting-edge semiconductor device development platform, where he is currently Director of SiC Research & Development Center. He is also a professor emeritus at Tohoku University. His significant scientific achievements earned him Ichimura Award (2008) in the New Technology Development Foundation, Prizes for Science and Technology; The Commendation for Science and Technology by the Minister of Education, Culture, Sports, Science and Technology (2009), Plasma Prize in American Vacuum Society (2010) and IEEE NTC Distinguished Lecturers (2019). Additionally, he has been elected as a “Distinguished Professor” of Tohoku University, a “Fellow” of the Japan Society of Applied Physics (JSAP) since 2008, a “Fellow” of American Vacuum Society (AVS) since 2009 and a also “Fellow” of Institute of Electrical and Electronics Engineers (IEEE) since 2018.